

## Poster #SUPTEV002

### Application of Plasma Electrolytic Polishing onto SRF Substrates

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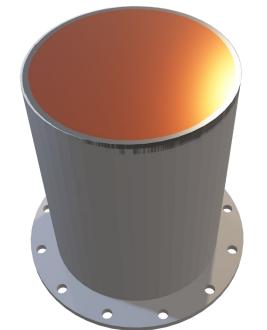


The scope of the work is to show the possibility of PEP application onto SRF substrates.

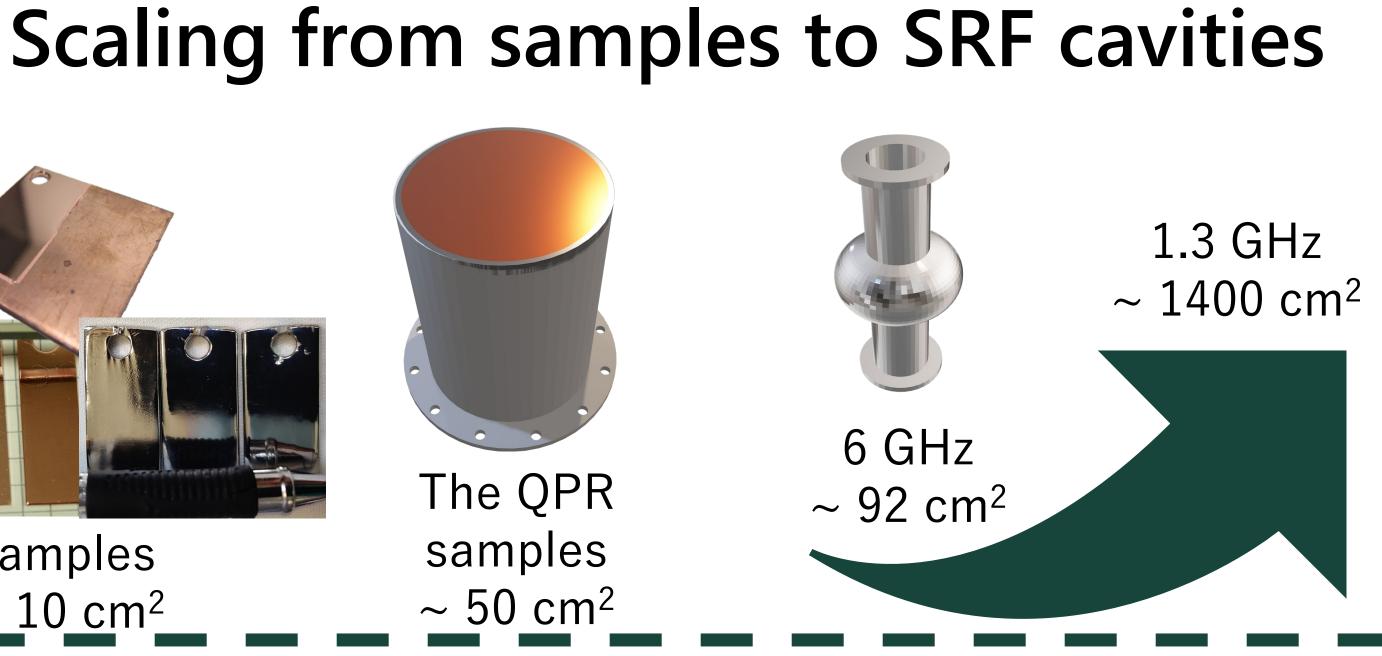
Work is showing possible system configuration and theirs's main challenges.

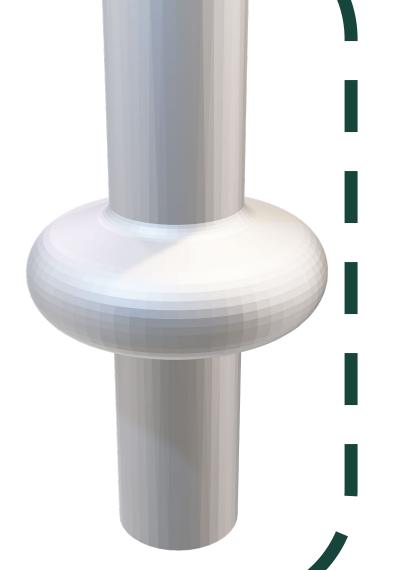


Samples  $\sim 10 \text{ cm}^2$ 



The QPR samples  $\sim 50 \text{ cm}^2$ 



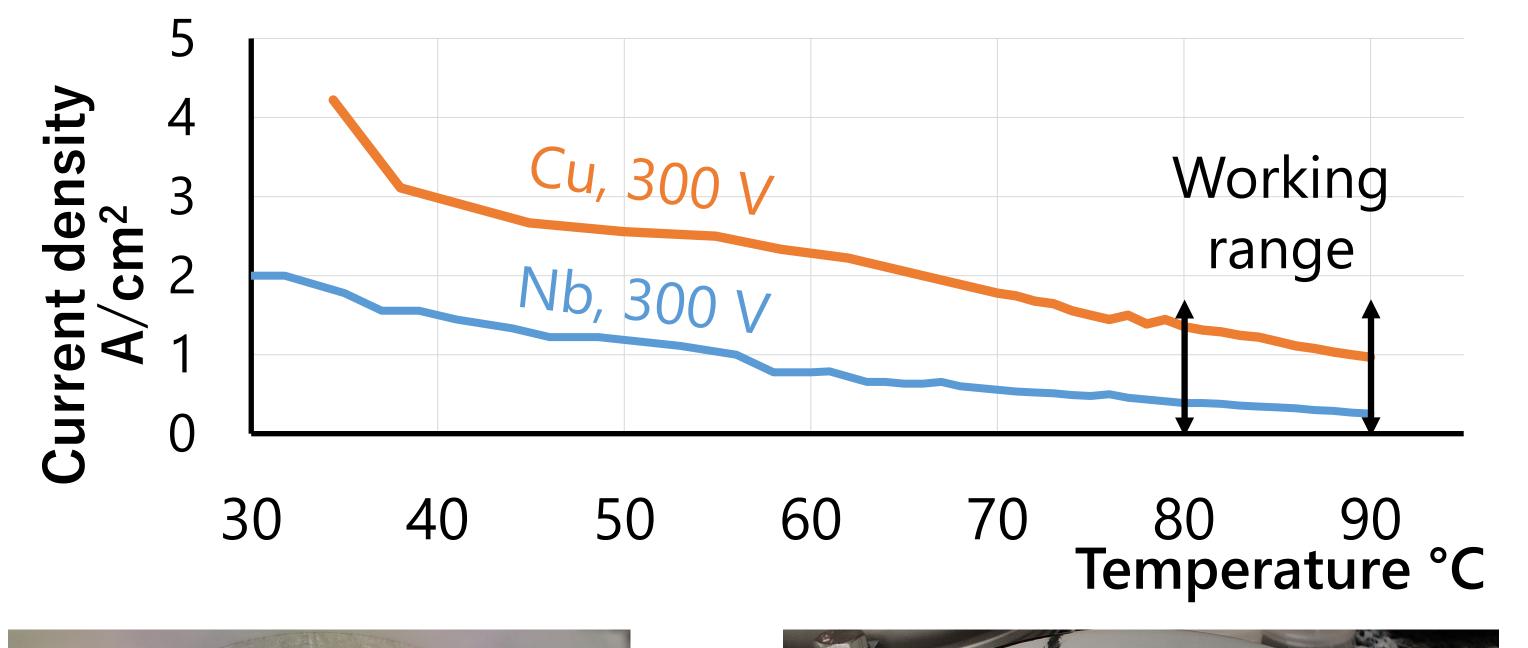


#### Requirements Caption

DC Power supply working at >300V 0,4-1,7 A/cm<sup>2</sup> Power delivery Water coil cooling / N<sub>2</sub> cooling / jacketed bath Solution cooling

Cathode/Anode ratio High cathode area, double cathode.

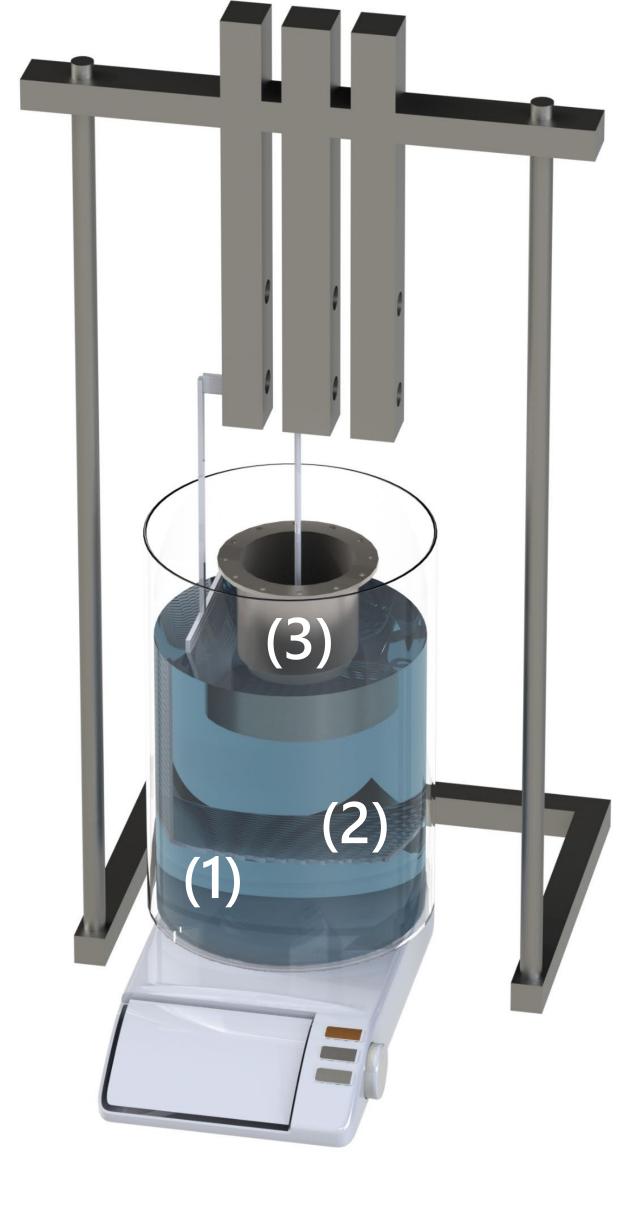
A range of 70-90℃ Working temperature



# 60 min 100 μm min 30 μm

### PEP of QPR sample

Nb/Cu and Nb QPR samples were polished in the waterbased diluted salt solution, at 80-90°C range. Cooling was supported with a N<sub>2</sub> fluxing inside the beaker (1). As a cathode (2) was chosen Ti mesh placed under the workpiece (3 - anode).





Initial surface of Nb QPR sample presented a pattern after wrong BCP processing. Scratches and peaks had a significant difference in height. Test Cu QPR sample has almost smooth surface, machined by lathe.

Smooth surface obtained in both cases. Nb QPR sample is mirror like reflected with slightly visible pattern. Cu QPR sample present some visible peaks and oxidised Nb border.

#### Conclusions

In this work it was shown the application of PEP as a preparation tool for SRF needs. Main requirements are described. PEP study should not stop only on phenomenological aspects, since polishing setups play significant role in successful processing.



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